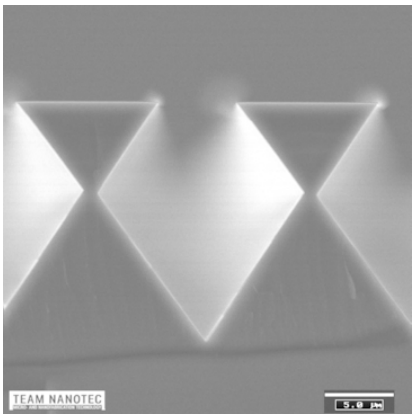
TEAM NANOTEC
MICRO- AND NANOFABRICATION TECHNOLOGY



I2FSR - Improved Flared Silicon Ridge

Line with sharp, overhanging edges.

Specifications

Material	Silicon coated with Siliconnitride
Width of line	~ 2 µm
Depth of line	> 4 µm
Overhang	> 250 nm
Overhang slope angle	~ 35°
Top corner radius	< 10 nm
Edge roughness	< 10 nm

Probe tip characterizers are used to check the shape and the dimension of the probe tip.

Each cell is numbered, which facilitates recalibration at the identical position.

Layout:
81 cells on 1 x 1 mm area, on 6 x 6 mm silicon chip

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